

Title (en)

Polyhydric phenol compound and positive resist composition comprising the same.

Title (de)

Polyhydrisches Phenolderivat und dieses enthaltende Positivresistzusammensetzung.

Title (fr)

Dérivé de phénol polyhydrique et composition de réserve positive le contenant.

Publication

EP 0505987 A1 19920930 (EN)

Application

EP 92105060 A 19920324

Priority

JP 6002491 A 19910325

Abstract (en)

A polyhydric phenol compound of the formula: <CHEM> wherein R1 to R5 are independently a hydrogen atom, an alkyl group, an alkenyl group, a cycloalkyl group or an aryl group, provided that at least one of R1 and R2 is an alkyl group, an alkenyl group, a cycloalkyl group or an aryl group, and its quinone diazide sulfonate which gives a positive resist composition having improved sensitivity and a good depth of focus.

IPC 1-7

C07D 311/64; **G03F 7/022**

IPC 8 full level

C07D 311/64 (2006.01); **G03F 7/022** (2006.01); **H01L 21/027** (2006.01)

CPC (source: EP KR US)

C07D 311/04 (2013.01 - KR); **C07D 311/64** (2013.01 - EP US); **G03F 7/0226** (2013.01 - EP US)

Citation (applicant)

EP 0363978 A2 19900418 - SUMITOMO CHEMICAL CO [JP]

Citation (search report)

[A] EP 0363978 A2 19900418 - SUMITOMO CHEMICAL CO [JP]

Cited by

EP0699670A3; US5726257A; US5916683A; EP0688770A3; US5698717A; EP0582309A3; US5556995A; US6469109B2; EP0695740A1

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